

Ni Sputtering Film using Sputter#3 (8-18-2016)

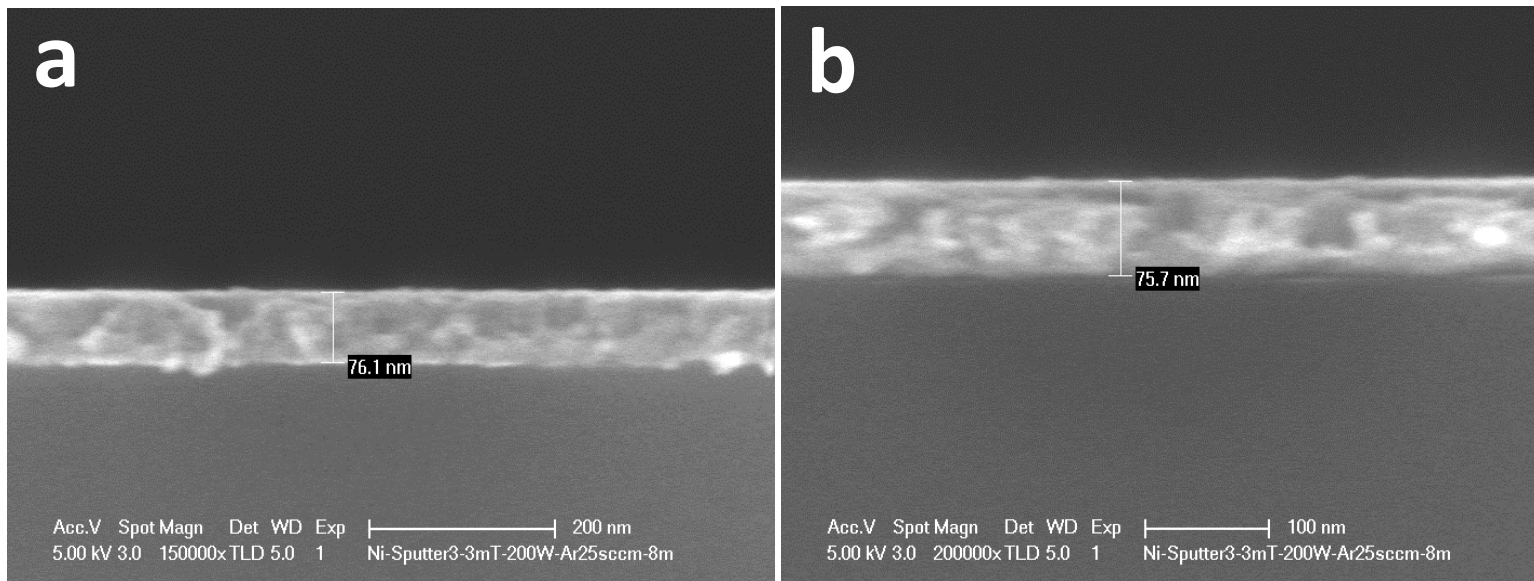
Condition: 3 mT, 200 W (389 V), Ar flow-rate=25 sccm, 44mm/4 (tilt angle), and Sputtering Time=480 seconds.

Result:

1) Film thickness measured by Ellipsometer=75.1 nm.

2) Ni Sputtering Rate=9.4 nm/min.

Figure 1 (a) and (b) Profile of Ni film; (c) Ni film surface (titled at 70°).



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Acc.V Spot Magn Det WD Exp |—————| 2 μ m
5.00 kV 3.0 12000x TLD 5.3 1 Ni-Sputter3-3mT-200W-Ar25sccm-8m

Figure 2 Film Thickness measured by Ellipsometer.

